

Supplementary Materials for
**Origin of ultra-wide temperature dielectric stability and
dynamic behavior of nanoregions in $0.6\text{Bi}(\text{Mg}_{0.5}\text{Ti}_{0.5})\text{O}_3$ -
 $0.4\text{Ba}_{0.8}\text{Ca}_{0.2}(\text{Ti}_{0.875}\text{Zr}_{0.125})\text{O}_3$**

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Captions of Figures

Fig. S1. Sketch of the dynamics of two kinds of PNRs of a re-entrant relaxor.

Comparison of comprehensive dielectric properties of 0.6BMT-0.4BCZT and 0.6Bi(Mg_{0.5}Ti_{0.5})O₃-0.4Ba_{0.8}Ca_{0.2}TiO₃ (0.6BMT-0.4BCT);¹ 0.6Bi(Mg_{0.5}Ti_{0.5})O₃-0.4Ba_{0.8}Ca_{0.2}(Ti_{0.875}Nb_{0.125})O₃ (0.6BMT-0.4BCNT);¹ 0.82(0.94Na_{0.5}Bi_{0.5}TiO₃-0.06BaTiO₃)-0.18K_{0.5}Na_{0.5}NbO₃ [0.82(0.94NBK-0.06KBT)-0.18KNN];² 0.75K_{0.5}Bi_{0.5}TiO₃-0.25BiScO₃ (0.75KBT-0.25BS);³ Bi_{0.5}Na_{0.5}TiO₃-0.03Yb₂O₅ (BNT-0.03Yb) for 1 MHz.⁴

Fig. S2. (a) The surface SEM images of 0.6BMT-0.4BCZT; (b)The statistic

distributions of the gain size in ceramics using Gauss distribution.

Fig. S3. (a) HRTEM image of using Inverse Fourier transform, (b) nano-scale-ordered structure and (c), (d) disorder structure.

Fig. S4. Variation of the gray value of the corresponding (a), (b), (c) and (d) HRTEM images presented in Fig. S3.

Fig. S5. (a) Temperature dependence of main relaxation time according to the M'' peak. The purple line is the Arrhenius and Volgel-Fulcher fitting, (b) permittivity variation of the ratio of $\varepsilon_\infty(T)$ to $\varepsilon_{1\text{ MHz}}(T)$ as a function of temperature in the 633 K to 973 K.

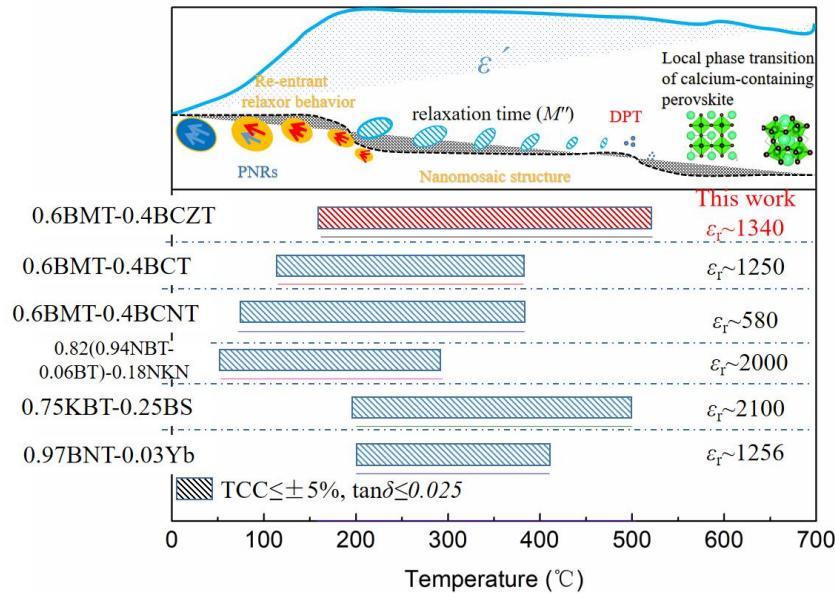


Fig. S1

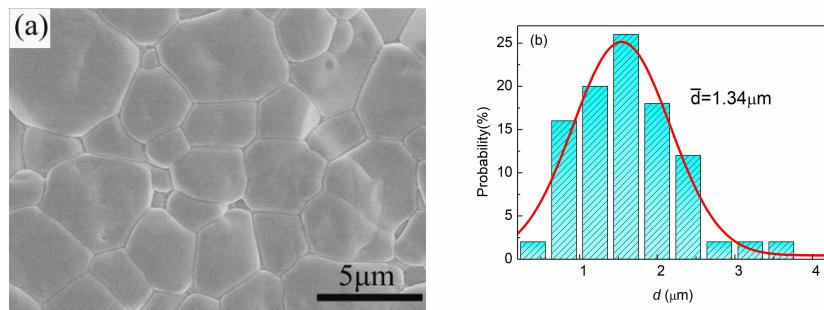


Fig. S2

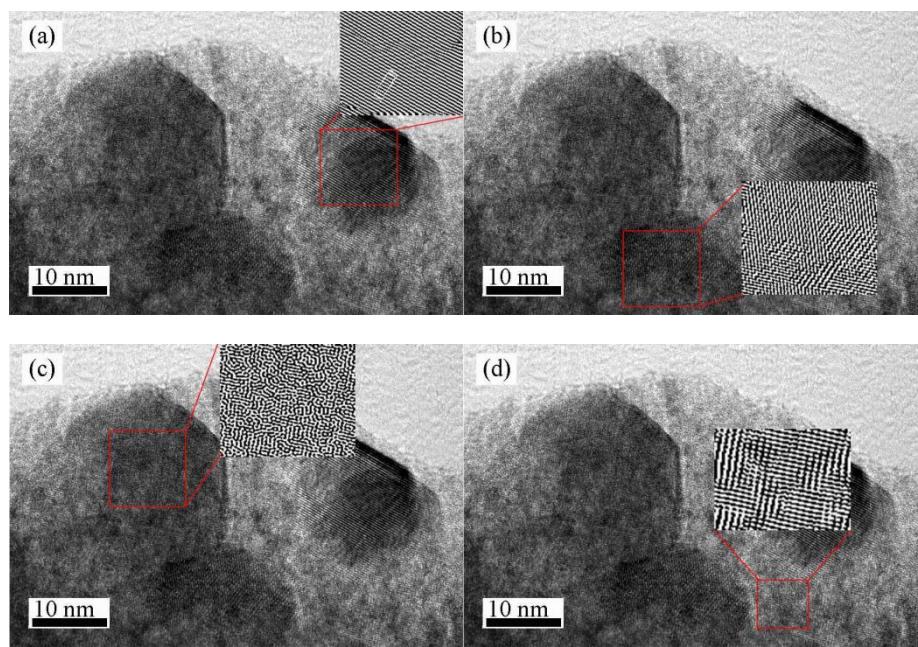


Fig. S3

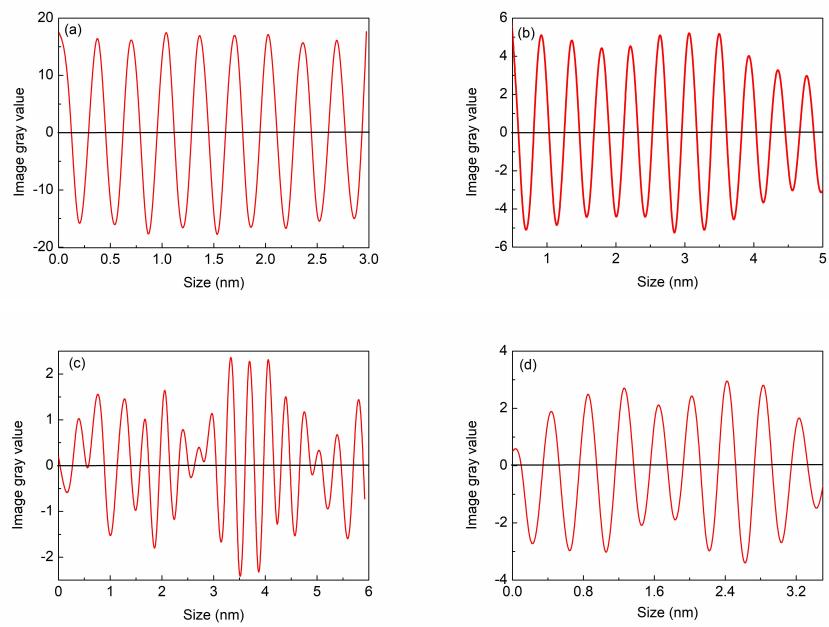


Fig. S4

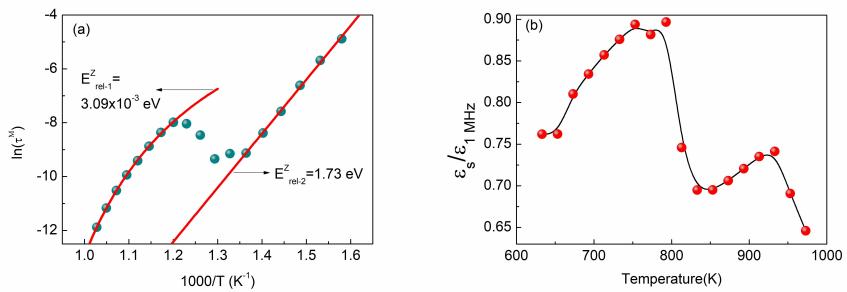


Fig. S5

References

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